

INF-119

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: GRIT SCHWALBE ET AL. Serial No.: NEW APPLICATION Filed: December 1, 2003 For: METHOD FOR PATTERNING DIELECTRIC LAYERS ON SEMICONDUCTOR SUBSTRATES	Art Unit: Unknown Examiner: Not Yet Assigned
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INFORMATION DISCLOSURE STATEMENT ACCOMPANYING FILING

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Applicants wish to make of record in the above-identified application the document or documents referenced on the attached Form PTO-1449. A copy of each reference is enclosed herewith.

The cited references are mentioned in the German Office Action (copy enclosed) of applicant's corresponding German patent application and are believed relevant for at least that reason.

It is respectfully requested that the information be expressly considered during the prosecution of this application, and that each reference be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

Inventor: Grit SCHWALBE et al.
Serial No. New Application
Art Unit: Unknown

Attorney Docket No. INF-119
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This submission does not represent that any referenced document is material or constitutes "prior art." If it should be determined that one or more of the referenced documents constitute "prior art" under United States law, Applicants reserve the right to present to the Office the relevant facts and law regarding the appropriate status of the reference or references.

Applicants further reserve the right to take appropriate action to establish the patentability of the disclosed invention over any referenced document, should it be applied against the claims of the present application.

SHAW PITTMAN LLP
1650 Tysons Boulevard
McLean, VA 22102
Tel: 703/770-7900

Date: December 1, 2003

Respectfully submitted,

GRIT SCHWALBE ET AL.

By:



Michael A. Oblon
Registration No. 42,956

INFORMATION DISCLOSURE CITATION <i>(Use several sheets if necessary)</i>				ATTY DOCKET NO. INF-119		SERIAL NO. New Application	
				GRIT SCHWALBE ET AL.			
				FILING DECEMBER 1, 2003		GROUP Unknown	

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
		5,660,681	08/26/97	FUKUDA ET AL.	438	695	08/19/96
		6,232,237	05/15/01	TAMAOKA ET AL.	438	725	12/08/98
		6,235,453	05/22/01	YOU ET AL.	430	329	07/07/99
		2002/0076935	06/20/02	MAEX ET AL.	438	706	09/28/01
		2001/0005635	06/28/01	KITAGAWA	438	710	12/14/00
		2002/0146647	10/10/02	AOKI ET AL.	430	313	03/11/02
		2002/0164877	11/07/02	CATABAY ET AL.	438	694	05/02/01

FOREIGN PATENT DOCUMENTS								
*	EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO

OTHER DOCUMENTS <i>(Including Author, Title, Date, Pertinent Pages, Etc.)</i>			
			Article entitled "Limitation of HF-Based Chemistry for Deep-Submicron Contact Hole Cleaning on Silicides" by M.R. Baklanov et al. , J. Electrochem. Soc., Vol. 145, No. 9 September 1998 by The Electrochemical Society, Inc., pp 3240-3246. Article entitled "low-k dielectric etching" by D.J. Thomas et al., published March 2001 in Solid State Technology, pages107, 108, 112-116 (www.solid-state.com)
			Copy of German Office Action dated October 20, 2003

EXAMINER	DATE CONSIDERED
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*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.